

ABSTRACT

Fluid Handling Structure, Lithographic Apparatus and Device Manufacturing Method

A fluid handling structure is disclosed which is designed for all wet immersion lithography. The fluid handling structure has a first opening to provide fluid to a space between a final element of a projection system and a substrate and/or substrate table, a barrier to resist the flow of liquid out of the space between the fluid handling structure and the substrate, and a second opening, which opens into an area radially outwardly of the space, to provide a flow of fluid from the fluid handling structure onto a top surface of the substrate and/or substrate table radially outwardly of the space. A controller may be provided such that flow of fluid towards a center of the substrate table is greater than the flow of fluid in a direction away from the center of the substrate table.

[Figure 6]